

## Dynamics of the Dissociative Adsorption of Methane on Pt{110}(1 × 2)

A. V. Walker and D. A. King

*Department of Chemistry, University of Cambridge, Lensfield Road, Cambridge, CB2 1EW, United Kingdom*  
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An exhaustive molecular beam study of methane dissociation on Pt{110}(1 × 2) provides a new data base for modeling this process. Major new features include a sharp rise in dissociative sticking probability,  $s_0$ , with increasing translational energy,  $E_t$ , corresponding to a barrier of 238 meV, a dramatic increase in  $s_0$  at higher  $E_t$  with increasing vibrational energy, and a significant rise in  $s_0$  as  $E_t$  is lowered below  $\sim 100$  meV. It is concluded that the low energy process is a distinctive steering-assisted direct adsorption pathway. [S0031-9007(99)09442-9]

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The dissociative interaction between methane and a metal surface has been extensively studied as an example of *activated* adsorption. Early work [1,2] indicated an activation energy in the range of 310 to 420 meV. A consensus appears to be emerging from a series of molecular beam studies that this is a direct activated process [3–19]. In particular, Rettner *et al.* [9] on W{110} and Luntz and Bethune [11] on Pt{111}, working at translational energies above 100 meV, and Lee *et al.* [7] on Ni{111}, working over the narrower range 550 to 750 meV, showed that the dissociative initial (zero coverage) sticking probability  $s_0$  increases logarithmically with translational energy. Rettner *et al.* [9] and Lee *et al.* [7] also reported a strong increase in  $s_0$  with increasing incident vibrational energy, for which there is now a general consensus [3,6–10].

Recently Seets *et al.* [20–22] studied the dissociative adsorption of CH<sub>4</sub> on Ir{110} and Ir{111}. At incident energies above 100 meV they again report a significant increase in  $s_0$  with increasing energy, but at lower energies they reported a small upturn in  $s_0$ . Following the early work on the dissociative adsorption of N<sub>2</sub> on W{100} [23], this was assigned to a thermalized precursor mediated process. In this interpretation, the barrier to dissociation from the precursor state is larger than the barrier to desorption. In the present work, we observe a large, 100-fold increase in  $s_0$  as the incident translational energy is lowered from 100 to 25 meV and we discuss the mechanistic implications.

A range of models have been developed to describe the high translational energy activated dissociation process. Brass and Ehrlich [10], noting the strong influence of both *gas and surface temperature* on the process, proposed a complex mechanism involving three channels. Lee *et al.* [7] proposed that dissociation involved activation of the angular deformation mode of the CH<sub>4</sub> molecule, enabling a C-metal bond to be formed; here the translational energy is coupled to this deformation mode on impact. Luntz and co-workers [16,24] developed an alternative model, involving a concerted, direct dissociation of the incident molecule breaking a single C-H bond on impact. Here it is the C-H stretching mode which plays a critical role.

Finally, Ukraintsev and Harrison [25] adapted statistical unimolecular rate theory to develop a model in which direct dissociation is treated as occurring through energy randomizing collisions between incident molecules and local clusters of surface metal atoms.

The experiments were conducted using a supersonic molecular beam apparatus which has been described previously [26]. The sample was a clean single-crystal surface oriented to within 1° of the {110} plane and mechanically polished. Initially the Pt{110} surface was cleaned using prolonged Ar sputtering, annealing and oxygen treatments. Afterwards, the surface was cleaned by heating to 1240 K, oxygen treatment, and annealing at 950 K.

The sticking probability is defined as the ratio of the number of dissociatively adsorbed CH<sub>4</sub> molecules to the total number of molecules incident on the surface from the flux and time. In agreement with Solymosi [27], no other moieties from the breakup of methane were detected apart from C<sub>a</sub>. The amount of C<sub>a</sub> was determined by heating to 650 K to desorb H<sub>2</sub> and any CO adsorbed during the experiment, followed by titration with an O<sub>2</sub> beam to CO and CO<sub>2</sub>. We estimate that the uncertainty in the sticking probability is  $\pm 7\%$ .

The translational energy of the molecular beam, generated with 1 to 2 bars behind the nozzle, was determined using time-of-flight techniques, and the flux was measured using a stagnation tube. To increase or decrease the translational energy without altering the internal energy, methane was seeded in He, Ar, or Kr. The translational energy and the internal energy of CH<sub>4</sub> could be changed by heating or cooling the nozzle. The highest nozzle temperature used was 850 K; we have evidence for methane cracking at the Mo nozzle above 900 K. All data here are reported for normal incidence.

In presenting the CH<sub>4</sub> dissociative sticking probability data we have taken great care to separate the contributions from the translational and vibrational energy components of the incident molecule. The object has been to collect a comprehensive body of data so that the detailed contribution of these two energy modes can be analyzed over a wide range of translational energies. We estimate that the maximum rotational energy in these experiments is  $\sim 80$  K

( $J_{\max} \approx 3$ ); under these conditions, vibrational excitation is dominant, and we therefore ignore the former.

The variation of  $s_0$  with incident translational energy  $E_t$  in the range 25 to 690 meV, at a surface temperature of 400 K, is shown in Fig. 1. Each of the six curves corresponds to a constant nozzle temperature  $T_n$  and, hence, vibrational energy  $E_v$  in the range 300 to 800 K. The results display a range of important novel features which we highlight here. (i) At the lowest nozzle temperature (300 K),  $s_0$  is relatively high at low  $E_t$  ( $4 \times 10^{-4}$  at 25 meV) and falls sharply with increasing  $E_t$  to a minimum value of  $3 \times 10^{-6}$  at  $E_t = 100$  meV. (ii) In this range of low  $E_t$ , the sticking probability rises sharply with increasing vibrational energy; at  $E_t = 75$  meV the rise is from  $4.5 \times 10^{-6}$  at  $T_n = 300$  K to  $1.4 \times 10^{-4}$  at  $T_n = 800$  K. (iii) In the energy range of  $E_t$  between 100 and 190 meV,  $s_0$  rises sharply; the half-width of the linear derivative,  $\partial s_0 / \partial E_t$ , is  $\sim 20$  meV, which is close to the estimated energy spread of the incident beam,  $\sim 15$  meV, at these energies. There is therefore a sharp threshold indicative of a single, well-defined activation barrier for the dissociation process. As with the minimum in  $s_0$  as a function of  $E_t$ , the turning point or threshold energy  $E_t^0$  increases with increasing  $T_n$ . (iv) For incident translational energies above 170 to 240 meV, depending on  $T_n$ ,  $\ln s_0$  approaches an asymptotic value which is strongly dependent on vibrational energy, rising from  $\sim 3 \times 10^{-5}$  at  $T_n = 300$  K to  $\sim 9 \times 10^{-3}$  at  $T_n = 800$  K.

There are significant differences between the present results and a wide range of data obtained on other transition metal surfaces. Since, with the exception of the recent work of Seets *et al.* [20–22] on Ir{110} and Ir{100}, previous studies were restricted to the higher range of translational energies ( $\geq 100$  meV), important differences lie in this range. In particular, the present work demonstrates an unusually sharp rise in  $s_0$  with  $E_t$  at  $\sim 180$  meV, followed by a plateau for a given vibrational energy. All previous studies show a logarithmic increase in  $s_0$  with incident “translational” energy. However, the logarithmic

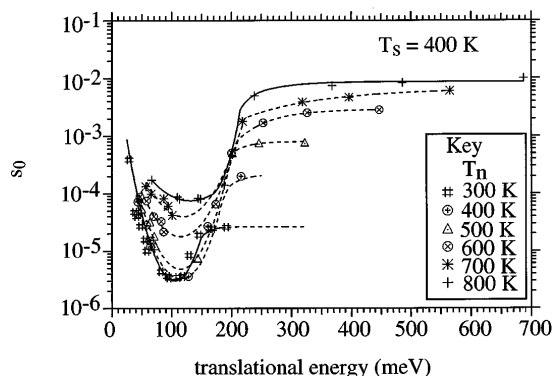


FIG. 1. Dependence of  $s_0$  on incident translational energy for methane dissociative adsorption at  $T_s = 400$  K; normal incidence and nozzle temperatures  $300 \leq T_n \leq 800$  K.

$s_0$  dependence collated, for example, by Schoofs *et al.* (see Fig. 6 in Ref. [12]) is the variation with *total* energy, i.e., translational plus vibrational energies, and includes data with nozzle temperature variations between 300 and 1000 K; only the data for Pt{111} was at constant nozzle temperature and, here, the nozzle temperature used, 993 K, is questionably high. The failure to previously observe a sharp threshold in  $s_0$  with translational energy may derive from (a) a failure to separate vibrational and translational contributions, and (b) the range of translational energies used being too high to observe the true threshold. On Pt{110}(1  $\times$  2), Luntz and Winters [16] determined  $s_0$  in a “bulb,” i.e., a nonbeam, experiment, at a nominal gas temperature of 300 K. Their  $s_0$  values range from  $4 \times 10^{-7}$  at  $T_s = 300$  K to  $2 \times 10^{-4}$  at  $T_s = 1000$  K, which match well with our low  $E_t$  data.

Each of the new results must be accounted for in a model for methane dissociation, but it is useful first to briefly summarize our studies of the influence of surface temperature,  $T_s$ , and isotopic substitution on the processes involved. We take the latter first. At surface temperatures between 400 and 1000 K,  $s_0$  was measured for both  $\text{CH}_4$  and  $\text{CD}_4$  at  $E_t = 95$  meV and  $T_n = 300$  K. At this value of  $E_t$ ,  $s_0$  increases from  $3.4 \times 10^{-6}$  at  $T_s = 400$  K to  $4.2 \times 10^{-5}$  at  $T_s = 1000$  K, and over the whole range  $s_0^{\text{CH}_4} / s_0^{\text{CD}_4} \approx 2$ , in agreement with Luntz and Winters [16]. However, the isotopic sticking probability was found to be sensitive to vibrational energy: At a fixed  $E_t = 188$  meV, at  $T_n = 300$  K, the ratio is 1.11, compared to 1.78 at  $T_n = 800$  K. This result is consistent with the observed sensitivity of  $s_0$  to vibrational excitation in the incident molecule; the population of the first excited states increases more for  $\text{CH}_4$  than for  $\text{CD}_4$  over this range of  $T_n$ .

Now we consider the influence of crystal temperature  $T_s$ . The results in Fig. 1 indicate two adsorption regimes: the first corresponds to translational energies below  $\sim 100$  meV, where  $s_0$  decreases with increasing  $E_t$ , and the second to energies above 100 meV, where  $s_0$  increases with increasing  $E_t$ . Each regime is considered separately.

The influence of  $T_s$  on  $s_0$  for the high translational energy regime is shown on a linear plot of  $s_0$  vs  $E_t$  in Fig. 2 for  $T_s$  between 400 and 1000 K, obtained at constant nozzle temperature,  $T_n = 800$  K. Since the energy spread of the incident molecular beam approximates to the width of the transition from low  $s_0$  to relatively high  $s_0$ , the threshold energy  $E_t^0$  for the onset of the high translational energy process is estimated from the point of inflection of these  $s_0$  vs  $E_t$  linear plots. This threshold energy shifts to lower values with increasing surface temperature. We note that *above*  $E_t^0$ ,  $s_0$  increases approximately linear with  $E_t$ . The dependence of  $E_t^0$  on  $T_s$  is also nearly linear:

$$\begin{aligned} E_t^0 &= (238 - 8 \times 10^{-2} T_s) \text{ meV} \\ &= (22.9 - 0.9RT_s) \text{ kJ/mol.} \end{aligned} \quad (1)$$

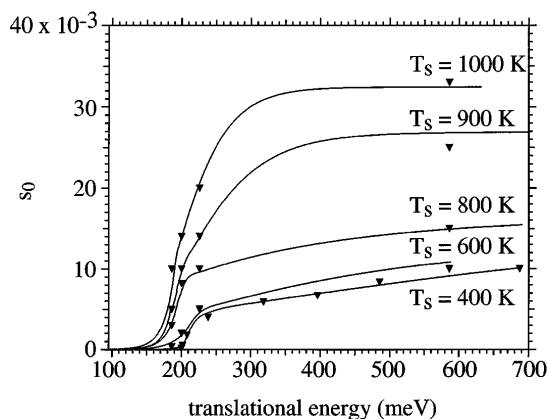


FIG. 2. Variation of  $s_0$  with  $E_t$  at surface temperatures between 400 and 1000 K; normal incidence  $T_n = 800$  K.

It is important to note that the measured threshold energy decreases linearly with thermal energy  $RT_s$  of the solid surface. Energy is provided for the dissociation process by *both* the incoming molecule *and* the surface, i.e., by both reactants. The incident  $\text{CH}_4$  translational energy is strongly coupled to, or randomized with, the phonon modes of the impacted region of the solid. Hence the true activation energy for the dissociative adsorption process is the limiting value of the threshold energy  $E_t^0$  at  $T_s = 0$  K which, from Eq. (1), is  $E_a = 238$  meV.

The influence of surface temperature was also studied in the low translational energy regime at  $E_t = 38$  meV, and again significant enhancement in  $s_0$  with increasing  $T_s$  was found: at  $E_t = 38$  meV and  $T_n = 300$  K,  $s_0 = 4 \times 10^{-5}$  at  $T_s = 400$  K and rises to  $4 \times 10^{-4}$  at  $T_s = 500$  K.

The role of vibrational motion in  $\text{CH}_4$  is more complex since, as mentioned in (iii) above,  $E_t^0$  increases with increasing  $T_n$  which is contrary to the anticipated trend. Thus at  $T_n = 400$  K, from Eq. (1), we derive a barrier height of  $\sim 160$  meV, compared with 238 meV at  $T_n = 800$  K. Vibrational excitation *inhibits* dissociation for  $E_t$  close to the threshold, despite the enormous increase at energies above threshold. We have considered the possibility that this inhibitive effect could be attributed to an increase in rotational energy of the incident molecule, but dismissed this due to the low rotational temperatures achieved in our beam,  $\leq 0.1T_n$  [28]. It is more likely that different vibrational modes of  $\text{CH}_4$  are involved in the enhancement of the process above threshold and in the increase in the threshold energy. We show below that the stretching modes produce the enhancement and hence conclude here that the barrier height for the direct activated process is probably increased when the *deformation* modes are excited. This result is inconsistent with both the quantum tunneling [24] and the unimolecular rate theory [25] models. In particular, in the latter model, randomization of the vibrational energy should lead to a decrease in  $E_t^0$  with increasing  $E_v$ , in line with the observed decrease with increasing  $T_s$ .

To evaluate which internal vibrational modes of  $\text{CH}_4$  are involved in enhancing  $s_0$  at low and high translational energies, we have used a simple two-state model analysis. Thus

$$s_0 = f_{\nu=0}s_0^{\nu=0} + f_{\nu=1}s_0^{\nu=1},$$

where  $f$  is the fraction of incident molecules in the given vibrational state and  $s_0^{\nu}$  is the appropriate sticking probability. Plots of  $\ln(s_0 - s_0^{\nu=0})$  vs  $1/T_n$  at  $E_t = 60$  meV are linear with  $s_0^{\nu=0} = 9 \times 10^{-6}$  (close to the experimental value at  $T_n = 300$  K),  $gs_0^{\nu=1} \approx 6 \times 10^{-3}$  (where  $g$  is the degeneracy of the mode involved), and a mode frequency  $\omega = 1400 \pm 200$   $\text{cm}^{-1}$ . This value of  $\omega$  spans the lowest frequency modes of  $\text{CH}_4$ , the  $\nu_4$  symmetric deformation mode at 1306  $\text{cm}^{-1}$ , and the  $\nu_2$  antisymmetric deformation at 1526  $\text{cm}^{-1}$ . From this analysis, at  $E_t = 60$  meV,  $s_0^{\nu=1}$  is  $2.5 \times 10^{-3}$ , about 300 times larger than  $s_0^{\nu=0}$ . We note that both  $s_0^{\nu=0}$  and  $s_0^{\nu=1}$  decrease as  $E_t$  is increased up to  $\sim 85$  meV.

In the high energy regime the vibrational analysis yields a linear plot with  $gs_0^{\nu=1} \approx 1$  and  $\omega = 2800 \pm 400$   $\text{cm}^{-1}$ . This frequency is close to the C-H stretching frequencies,  $\nu_1 = 2914$   $\text{cm}^{-1}$  and  $\nu_3 = 3020$   $\text{cm}^{-1}$ . In this regime, it would appear that the treatment of methane as a quasidiatomic molecule [24], R-H, may be justified. Provided that the combined methane translational and surface phonon energies are sufficient to surmount the barrier  $E_a$ , dissociative adsorption is strongly assisted by excitation of one C-H bond in the molecule; according to this analysis, the sticking probability approaches unity in the  $\nu = 1$  vibrationally excited state, a  $(2 \times 10^3)$ -fold increase over the ground state.

Now we turn to the question of direct adsorption and precursor state trapping. There are two possible models for the low  $E_t$  data, where  $s_0$  falls sharply with increasing  $E_t$ . This is the behavior anticipated for trapping into a weakly held precursor state, followed by dissociation [23], and this is the model favored by Seets *et al.* [20–22] for  $\text{CH}_4$  on Ir{111} and Ir{110}. However, in recent experimental studies of  $\text{D}_2$  on Pt{100} [29] and theoretical studies of  $\text{H}_2$  adsorption [30,31], the increase in  $s_0$  at low  $E_t$  has been attributed to dynamic steering in a direct dissociation process, the steering at low energies being required by the topology of the potential energy surface. Since the lifetimes of excited vibrational states of adsorbates on metal surfaces ( $\sim 1$  to 50 ps) [32] are similar to the lifetime of trapped  $\text{CH}_4$  at  $T_s$  from 400 to 800 K ( $\sim 10$  to 1 ps) [33], the current observation that vibrational excitation of incident  $\text{CH}_4$  has a favorable effect on  $s_0$  (Fig. 1) is equivocal. Accommodation of the incident translational energy, with incomplete accommodation of the vibrational energy, could assist the activated transition from precursor to dissociated states. Increased vibrational excitation in the incident molecule and phonon excitation in the surface both increase the rate of dissociation, provided

that the translational energy in the incident molecule is sufficiently low for translational trapping to occur, as found. However, we note that a *different* vibrational mode is involved in this low  $E_t$  process. This implies a different potential energy pathway for the reaction, which is not the activated pathway observed at high  $E_t$ . This indicates that at low  $E_t$  the incident methane molecule, for a given set of impact parameters, can be steered into a very low activation barrier dissociation process which cannot be accessed as  $E_t$  is increased.

This work demonstrates again that surface temperature also plays a strong role in enhancing direct dissociative adsorption processes [16–18,24,29]. Here both the direct activated process with a barrier height of 160 to 238 meV, depending on CH<sub>4</sub> vibrational energy, and the steering process are assisted by surface temperature. In the former case the threshold barrier for adsorption at a given CH<sub>4</sub> translational energy decreases with increasing thermal energy of the surface, given by Eq. (1), and is readily understood. However, the activation energy for the process observed at low  $E_t$  is apparently close to zero, since there is no sign of the  $s_0$  vs  $E_t$  plot (Fig. 1) reaching a limiting low value as  $E_t \rightarrow 0$  meV—the plot appears to be extrapolating towards  $s_0 = 1$ . Here the surface temperature plays a similar role to that of excitation of the deformation mode in the incoming molecule: Phonon excitation of the surface can lead to a higher reactivity of surface metal atoms, as in the model of Pasteur *et al.* [29].

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